OIPE JC54
AUG 26 2005
PATENT & TRADEMARK OFFICE

IFW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applicant:		§		
	Robert P. Meagley et al.	§	Art Unit:	1765
		§		
Serial No.:	10/679,793	§	Examiner:	Kin Chan Chen
		§		
Filed:	October 6, 2003	§	Atty Docket:	ITL.1018US
		§		P16705
For:	Increasing the Etch	§		
	Resistance of Photoresists	§	Assignee:	Intel Corporation
		§		

Mail Stop **Amendment**
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

SUPPLEMENTAL RESPONSE
TO RESTRICTION REQUIREMENT

Sir:

In response to the office communication mailed August 3, 2005, please amend the above-referenced patent application as follows:

Date of Deposit: August 24, 2005
I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

Cynthia L. Hayden

Cynthia L. Hayden